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(54) Title: IMPROVED STEREOLITHOGRAPHY MACHINE

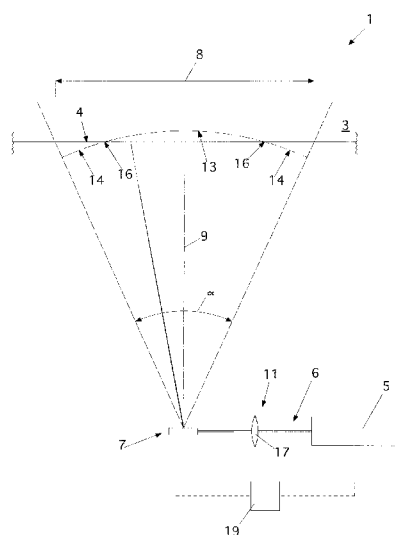


Fig. 2

(57) Abstract: The invention is a stereolithography machine (1) comprising: a container (2) containing a base material (3) that defines an outer surface (4) delimiting it; a light emitting unit (5) suited to emit a light beam (6); a light reflecting device (7) suited to deviate the light beam (6) towards an incidence area (8) belonging to the outer surface (4); a logic control unit (19) suited to control the light reflecting device (7) in such a way that the light beam (6) is selectively incident on an operating area (10) belonging to the incidence area (8); an optical unit (11) suited to focus the light beam (6) on a focal surface (12) where the light beam (6) has minimum cross section (15). The optical unit (11) is arranged between the light emitting unit (5) and the light reflecting device (7), the light emitting unit (5) and the optical unit (11) being configured in such a way that the ratio between the maximum diameter of the intersection area of the light beam (6) with the operating area (10) and the diameter (W_F) of the minimum cross section (15) does not exceed 1.15.